Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	15	punsalan near david.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:08
L2	26	lazaroff near dennis.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:09
L3	51	beatty near christopher.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:09
L4	0	"10695306"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:10
L5	1	"10/695306"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:10
L6	36	(liquid near precursor) and (inorganic near3 salt) and (ceramic).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:14
L7	5	(liquid near precursor) and (inorganic near3 salt) and (photoresist or resist) and (ceramic).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:29
L8	22	(liquid near precursor) and (inorganic near3 salt) and (photoresist or resist) and (ceramic)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:29
L9	0	8 and ((resist or photoresist) with (inorganic))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:30

L10	0	8 and ((resist or photoresist) same (inorganic))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:30
L11	12	8 and ((resist or photoresist) same (salt or metal))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:36
L12	12	8 and ((resist or photoresist or mask) same (salt or metal))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:37
L13	12	8 and ((resist or photoresist or photomask or photo-mask) same (salt or metal))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:37
L14	442	(presursor)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:37
L15	249346	(precursor)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:37
L16	31029	liquid near film	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:38
L17	144298	(inorganic) near3 (metal or salt)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:38
L18	568890	(photoresist or resit or mask or photomask or photo-mask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:39
L19	5	7 and 8	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:39

L20	7469	17 and 18	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:39
L21	2701	15 and 20	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:39
L22	104	16 and 21	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:39
L23	91	22 and dissolv$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:59
L24	1	23 and (inorganic) near3 (metal or salt) near15 (dissolv$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:47
L25	9	23 and (photoresist or photo-resist or resist) near15 (dissolv$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 14:47
L26	15	23 and (etch$3 or pattern$3 or remov$3) near25 (liquid near film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 15:13
L27	8	"4952556".pn. or "20020083863" or "5942376".pn. or "20030157250"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 15:34
L28	135	(salt) near15 (dissolv$3) near15 (photoresist or photo-resist or resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 15:44
L29	12	28 and (precursor)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 15:45

L30	4206	(salt) near15 (dissolv$3) and (photoresist or photo-resist or resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 15:44
L31	231	30 and (precursor) near3 (liquid or solution)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 15:45
L32	89	31 and (pattern$3) near15 (film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 15:46
L33	88	32 and (oxide$1 or electrode$1 or ceramic$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 15:46
L34	74	33 and inorganic	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 15:47
L35	25	33 and (inorganic near5 salt)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 15:47
L36	25	33 and (inorganic near3 salt)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 15:47
L37	25	33 and (inorganic near2 salt)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 15:47
L38	25	37 and (wafer or substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:08
L39	0	38 and (inorganic near2 salt) same (photoresist or photo-resist or resist or photosens$3 or photo-sens$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:09

L40	25	38 and (inorganic near2 salt) and (photoresist or photo-resist or resist or photosens$3 or photo-sens$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:10
L41	25	40 and (pattern$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:10
L42	25	40 and (pattern$3) same (film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:10
L43	25	40 and (pattern$3) with (film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:22
L44	1	40 and (pattern$3) with (liquid near5 film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:11
L45	1	40 and (pattern$3) same (liquid near5 film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:11
L46	25	43 and (dissolv$3 or dislodg$3 or dilut$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:13
L47	6	43 and (dissolv$3 or dislodg$3 or dilut$3) with (photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:14
L48	0	43 and (dissolv$3 or dislodg$3 or dilut$3) with (photo-resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:15
L49	1	43 and (dissolv$3 or dislodg$3 or dilut$3) with (resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:15

L50	10	43 and (dissolv$3 or dislodg$3 or dilut$3) same (resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:15
L51	14	43 and (dissolv$3 or dislodg$3 or dilut$3) same (photoresist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:15
L52	25	43 and (electro$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 18:37
L53	20	43 and (electrolyte)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:23
L54	20	53 and electrode	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:23
L55	15	54 and (electrolyte near25 electrode)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:28
L56	6	54 and ((electrolyte near25 electrode) with (film))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:33
L57	14	46 and miscib$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:34
L58	0	57 and (precursor) near25 (miscib$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:34
L59	0	57 and (precursor) with (miscib$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:34

L60	0	57 and (precursor) same (miscib$3)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 17:34
L61	0	(phtoresist) near10 (water-soluble)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 18:38
L62	468	(photoresist) near10 (water-soluble)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 18:41
L63	146	62 and (pattern$3 near5 film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 18:38
L64	7	63 and precursor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 18:43
L65	0	(photoresist) near10 (water near unsoluble)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 18:41
L66	0	(photoresist) near10 (water near un-soluble)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 18:41
L67	0	(photoresist) near10 (water near dissoluble)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 18:42
L68	0	(photoresist) near10 (water near disoluble)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 18:42
L69	0	(photoresist) near10 (water near dis-oluble)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 18:42

L70	0	(photoresist) near10 (water near dis-soluble)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 18:42
L71	520	(photoresist) near5 (water near soluble)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 18:44
L72	1	71 and liquid near precursor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 18:43
L73	42	(photoresist) near5 (no$1) near15 (water near soluble)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 18:46
L74	0	73 and liquid near precursor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 18:45
L75	1	73 and precursor	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/08/02 18:45